

FORM PTO-1449 (modified)  
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# INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: FINDERS et al.

Appln. No.: TO BE ASSIGNED

Filing Date: January 28, 2004

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Page

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of

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Examiner: *Euteneier*

Group Art Unit: *2951*

## U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
<i>AR</i>	AR	6,042,998	03/2000	BRUECK et al.			
<i>BR</i>	BR	6,320,648	11/2001	BRUECK et al.			
	CR						
	DR						
	ER						
	FR						
	GR						
	HR						
	IR						
	JR						
	KR						
	LR						
	MR						
	NR						

## FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name		Abstract		Readily Available	
							Enclosed	No	Enclose	No
	OR									
	PR									
	QR									
	RR									
	SR									
	TR									

## OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

<i>UR</i>	UR	Ooki et al., "A Novel Super-Resolution Technique for Optical Lithography – Nonlinear Multiple Exposure Method," <i>Jpn. J. Appl. Phys.</i> 33:L177 – L179 (1994)							
	VR								
	WR								
	XR								
	YR								
	ZR								
	AAR								
	BBR								
	CCR								

Examiner

*Kevin*

Date Considered:

*9.19.05*

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.